





























						<b>TRW 22</b>
I	Ratio to	o VAX	(: <u>Ti</u>	me:	Weigh	ted Time:
Program	Before	After	Before	After	Before	After
gcc	30	29	49	51	8.91	9.22
espresso	35	34	65	67	7.64	7.86
spice	47	47	510	510	5.69	5.69
doduc	46	49	41	38	5.81	5.45
nasa7	78	144	258	140	3.43	1.86
li	34	34	183	183	7.86	7.86
eqntott	40	40	28	28	6.68	6.68
matrix300	78	730	58	6	3.43	0.37
fpppp	90	87	34	35	2.97	3.07
tomcatv	33	138	20	19	2.01	1.94
Mean	54	72	124	108	54.42	49.99
		Geome	etric	Arithm	etic We	ighted Arith.













■ With lines ca. 0.18µm wide





 Highly magnified scanning electron microscope (SEM) view of IBM's six-level copper interconnect technology in an integrated circuit chip. The aluminum in transistor interconnections in a silicon chip has been replaced by copper that has a higher conductivity interconnect by a silicon chip has been replaced by copper that has a higher conductivity (by nearly 40%) and also a better ability to carry higher current densities without electromigration. Lower copper interconnect resistance means higher speeds and lower RC constants (Photograph courtesy of IBM Corporation, 1997.)









Intel technicians monitor wafers in an automated wet etch tool. The process cleans the wafers of any excess process chemicals or contamination.o)





					Intel	x86/P	entium Family
CPU	Year	Data Bus	Max. Mem.	Transistors	Clock MHz	Av. MIPS	Level-1 Caches
8086	1978	16	1MB	29K	5-10	0.8	
80286	1982	16	16MB	134K	8-12	2.7	
80386	1985	32	4GB	275K	16-33	6	
80486	1989	32	4GB	1.2M	25-100	20	8Kb
Pentium	1993	64	4GB	3.1M	60-233	100	8K Instr + 8K Data
Pentium Pro	1995	64	64GB	5.5M +15.5M	150-200	440	8K + 8K <sub>+</sub> Level2
Pentium II	1997	64	64GB	7M	266-450	466-	16K+16K + L2
Pentium III	1999	64	64GB	8.2M	500-1000	1000-	16K+16K + L2
Pentium IV	2001	64	64GB	42M	1300-2000		8K + L2
On On	l-line	manu detai	ıals: <u>h</u> ı ls: <u>htt</u> r	ttp://x86.ddj p://www.san	.com/intel. dpile.org/i	<u>doc/386m</u> a32/index.	<u>anuals.htm</u> <u>htm</u>



						Real		ona exampi
Chip N	Metal layers	Line width	Wafer cost	Defect /cm <sup>2</sup>	Area mm <sup>2</sup>	Dies/ wafer	Yield	Die Cost
386DX	2	0.90	\$900	1.0	43	360	71%	\$4
486DX2	3	0.80	\$1200	1.0	81	181	54%	\$12
PowerPC 6	01 4	0.80	\$1700	1.3	121	115	28%	\$53
HP PA 710	03	0.80	\$1300	1.0	196	66	27%	\$73
DEC Alpha	3	0.70	\$1500	1.2	234	53	19%	\$149
SuperSPAF	RC 3	0.70	\$1700	1.6	256	48	13%	\$272
Pentium	3	0.80	\$1500	1.5	296	40	9%	\$417











<ul> <li>Performance Summary needs good benchmarks and good ways to summarize performance</li> <li>Transistors/chip for microprocessors growing via "Moore's Law" 2X 1.5/yrs</li> <li>Disk capacity (so far) is growing at a faster rate over the last 4-5 years</li> <li>DRAM capacity is growing at a slower rate over the last 4-5 years</li> <li>In general, Bandwidth improving fast, latency improving a slower state over the state</li></ul>	Summ	ary
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■In general, Bandwidth improving fast, latency improving	DRAM capacity is growing at a slower rate over the las 4-5 years	;t
siowly	In general, Bandwidth improving fast, latency improving slowly	1



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